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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/709,907	06/04/2004	Douglas D. Coolbaugh	BUR920040156US1	3906	
29154	7590 03/26/2007 .		EXAMINER		
FREDERICK V Gibb & Rahma			HA, NG	JYEN T	
2568-A RIVA			ART UNIT	PAPER NUMBER	
SUITE 304 ANNAPOLIS, MD 21401		2831			
SHORTENED STATUTOR	RY PERIOD OF RESPONSE	MAIL DATE	DELIVER	DELIVERY MODE	
3 MONTHS		03/26/2007	PAPER		

Please find below and/or attached an Office communication concerning this application or proceeding.

If NO period for reply is specified above, the maximum statutory period will apply and will expire 6 MONTHS from the mailing date of this communication.

				# EK
		Application No.	Applicant(s)	
Office Action Comments		10/709,907	COOLBAUGH ET AL.	
Office Actio	n Summary	Examiner	Art Unit	
		Nguyen T. Ha	2831	
The MAILING DA	TE of this communication ap	opears on the cover sheet t	with the correspondence address	,
WHICHEVER IS LONGI - Extensions of time may be avail after SIX (6) MONTHS from the If NO period for reply is specifie Failure to reply within the set or	ER, FROM THE MAILING I able under the provisions of 37 CFR 1 mailing date of this communication. d above, the maximum statutory perior extended period for reply will, by statulater than three months after the mailing	DATE OF THIS COMMUN. 136(a). In no event, however, may a d will apply and will expire SIX (6) MO tte, cause the application to become	a reply be timely filed DNTHS from the mailing date of this communica ABANDONED (35 U.S.C. § 133).	
Status				
1) Responsive to cor	nmunication(s) filed on 15	<u>March_2007</u> .		
2a) This action is FINA	AL . 2b)⊠ Th	is action is non-final.		
3) ☐ Since this applicat	ion is in condition for allow	ance except for formal ma	atters, prosecution as to the merits	s is
closed in accordar	nce with the practice under	Ex parte Quayle, 1935 C.	.D. 11, 453 O.G. 213.	
Disposition of Claims			Ž.	
4)⊠ Claim(s) <u>1-18</u> is/aı	e pending in the applicatio	n.		
*	laim(s) <u>15-28</u> is/are withdra	awn from consideration.		
5) Claim(s) is/				
6)⊠ Claim(s) <u>1-6 and 8</u>				
7)⊠ Claim(s) <u>7 & 14</u> is		/a- alaatia		
	e subject to restriction and/	or election requirement.		
Application Papers				
9) ☐ The specification is	objected to by the Examir	ner.		
10)☐ The drawing(s) file	d on is/are: a)∏ ac	cepted or b) objected to	by the Examiner.	
•	equest that any objection to the	• • • • • • • • • • • • • • • • • • • •	· ·	
<u> </u>		·	ig(s) is objected to. See 37 CFR 1.12	
11) Ine oath or declara	ation is objected to by the E	Examiner. Note the attach	ed Office Action or form PTO-152	
Priority under 35 U.S.C. §	119			
12) Acknowledgment is	s made of a claim for foreig	n priority under 35 U.S.C.	§ 119(a)-(d) or (f).	
a)□ All b)□ Some	* c)☐ None of:			
	pies of the priority documer			
	pies of the priority documer			
•		•	n received in this National Stage	
	rom the International Bures		at received	
See the attached de	tailed Office action for a lis	scor the certified copies no	or received.	
		· ·		
Attachment(s)				

1) Notice of References Cited (PTO-892)

2) Notice of Draftsperson's Patent Drawing Review (PTO-948)

3) Information Disclosure Statement(s) (PTO/SB/08)
Paper No(s)/Mail Date Oloch.

4) Interview Summary (PTO-413)

6) Other: ____.

Paper No(s)/Mail Date. ___

5) Notice of Informal Patent Application

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DETAILED ACTION

Election/Restrictions

1. Applicant's election without traverse of claims 1-14 in the reply filed on 3/15/2007 is acknowledged.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 3. Claims 1-4, and 8-11 are rejected under 35 U.S.C. 102(e) as being anticipated by Ahn et al. (US 7,154,162).

Regarding claim 1, Ahn et al. disclose a metal-insulator-metal capacitor structure (figure 5) comprising:

- a lower conductor layer (120), wherein the lower conductor layer includes at least one lower capacitor plate and at least one wiring pattern (114);
- at least one capacitor dielectric (130) above the lower capacitor plate;
- at least one upper capacitor plate (140) above the capacitor dielectric; and
- a hardmask (155) above the upper capacitor plate.

Regarding claim 2, Ahn et al. disclose the hardmask is located along the top and sides of the upper capacitor plate (figure 5).

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Regarding claim 3, Ahn et al. disclose the hardmask has a pattern matching an etched pattern within the lower conductor layer (figure 5).

Regarding claim 4, Ahn et al. disclose the lower capacitor plate, the capacitor dielectric and the upper capacitor plate comprises a metal-insulator-metal capacitor (figure 5).

Regarding claim 8, Ahn et al. disclose a metal-insulator-metal capacitor structure (figure 5) comprising:

- a lower conductor layer (120), wherein the lower conductor layer includes
 at least one lower capacitor plate and at least one wiring pattern (114);
- at least one capacitor dielectric (130) above the lower capacitor plate;
- at least one upper capacitor plate (140) above the capacitor dielectric;
- an etch stop layer (150) on the upper capacitor plate; and
- a hardmask (155) on the etch stop layer.

Regarding claim 9, Ahn et al. disclose the etch stop layer is located along the top and sides of the upper capacitor plate (figure 5).

Regarding claim 10, Ahn et al. disclose the hardmask has a pattern matching an etched pattern within the lower conductor layer (figure 5).

Regarding claim 11, Ahn et al. disclose the lower capacitor plate, the upper capacitor plate comprise a metal-insulator-metal capacitor (figure 5).

Claim Rejections - 35 USC § 103

4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

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(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

5. Claims 5 & 12 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ahn et al. (US 7,154,162).

Regarding claims 5 & 12, Ahn et al. disclose all the claimed limitation discussed above with respect to claims 4 & 8, except for the metal-insulator-metal capacitor comprises a single metal-insulator-metal capacitor, wherein the structure further comprises at least one dual metal-insulator-metal capacitor, and wherein the dual metal-insulator-metal capacitor includes a second capacitor dielectric and a second upper plate. It would have been obvious to one having ordinary skill in the art at the time the invention was made to have the at least one dual metal-insulator-metal capacitor, and wherein the dual metal-insulator-metal capacitor includes a second capacitor dielectric and a second upper plate, since it has been held that mere

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duplication of the essential working parts of a device involves only routine skill in the art.

St. Regis Paper Co. v. Bemis Co. 193 USPQ 8.

6. Claims 5 & 12 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ahn et al. (US 7,154,162) in view of Tu et al. (US 6,720,232)

Regarding claims 6 &13, Ahn et al. disclose all the claimed limitation discussed above with respect to claims 1 &11, except for an insulator layer covering the hardmask, wherein the hardmask is distinct form the insulator layer. Tu et al. teach an insulator layer (64) covering the hardmask (62) figure 11. It would have been obvious to one having ordinary skill in the art at the time the invention was made to use the assembly as taught by Tu et al. in to Ahn et al., the modification of Tu et al. would be the benefit for Ahn et al. capacitor's to protect the hardmask layer.

Allowable Subject Matter

7. Claims 7 & 14 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

With respect to claims 7 & 14, the prior art alone or in combination does not teach the limitation of the spacing between wires in the wiring pattern is approximately one-third the height of the upper capacitor plate above the bottom of the lower capacitor plate.

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Citation Relevant of Prior Art

8. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

- a. Schwarz (US 6,972,265) discloses metal etch process selective to metallic insulating materials.
- b. Summerfelt (US 5,851,896) discloses conductive exotic nitride barrier layer for high dielectric constant material electrodes.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Nguyen T. Ha whose telephone number is 571-272-1974. The examiner can normally be reached on Monday-Friday from 8:30AM to 6:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Dean Reichard can be reached on 571-272-2800 ext. 31. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have guestions on access to the Private PAIR system, contact the Electronic

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Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800₇786-9199 (IN USA OR CANADA) or 571-272-1000.

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nguyen t. Ha

PRIMARY EXAMINER

NH V March 22, 2007